

L Number	Hits	Search Text	DB	Time stamp
1	296	(((((wafer substrate) near8 (hold\$3 pedestal chuck))) and (plasma ion) ) and (bias near3 volt\$6)) (((wafer substrate) near8 (hold\$3 pedestal chuck))) and (plasma ion) ) and (volt\$6))) and (monitor\$3 near5 ((bias near3 volt\$3) volt\$3))) and power	USPAT; US-PGPUB	2003/06/11 07:39
2	112	(((((wafer substrate) near8 (hold\$3 pedestal chuck))) and (plasma ion) ) and (bias near3 volt\$6)) (((wafer substrate) near8 (hold\$3 pedestal chuck))) and (plasma ion) ) and (volt\$6))) and (monitor\$3 near5 ((bias near3 volt\$3) volt\$3))) and power) and ((RF (radio near3 frequency)) near3 power)	USPAT; US-PGPUB	2003/06/11 07:26
3	33	(((((wafer substrate) near8 (hold\$3 pedestal chuck))) and (plasma ion) ) and (bias near3 volt\$6)) (((wafer substrate) near8 (hold\$3 pedestal chuck))) and (plasma ion) ) and (volt\$6))) and (monitor\$3 near5 ((bias near3 volt\$3) volt\$3))) and power) and ((RF (radio near3 frequency)) near3 power)) and (increas\$3 near3 power)	USPAT; US-PGPUB	2003/06/11 07:26
4	21	(((((wafer substrate) near8 (hold\$3 pedestal chuck))) and (plasma ion) ) and (bias near3 volt\$6)) (((wafer substrate) near8 (hold\$3 pedestal chuck))) and (plasma ion) ) and (volt\$6))) and (monitor\$3 near5 ((bias near3 volt\$3) volt\$3))) and power) and ((RF (radio near3 frequency)) near3 power)) and (decreas\$3 near3 power)	USPAT; US-PGPUB	2003/06/11 07:27
5	9	(((((wafer substrate) near8 (hold\$3 pedestal chuck))) and (plasma ion) ) and (bias near3 volt\$6)) (((wafer substrate) near8 (hold\$3 pedestal chuck))) and (plasma ion) ) and (volt\$6))) and (monitor\$3 near5 ((bias near3 volt\$3) volt\$3))) and power) and ((RF (radio near3 frequency)) near3 power)) and (increas\$3 near3 power)) and ((((((wafer substrate) near8 (hold\$3 pedestal chuck))) and (plasma ion) ) and (bias near3 volt\$6)) (((wafer substrate) near8 (hold\$3 pedestal chuck))) and (plasma ion) ) and (volt\$6))) and (monitor\$3 near5 ((bias near3 volt\$3) volt\$3))) and power) and ((RF (radio near3 frequency)) near3 power)) and (decreas\$3 near3 power))	USPAT; US-PGPUB	2003/06/11 07:27
6	4	(((((wafer substrate) near8 (hold\$3 pedestal chuck))) and (plasma ion) ) and (bias near3 volt\$6)) (((wafer substrate) near8 (hold\$3 pedestal chuck))) and (plasma ion) ) and (volt\$6))) and (monitor\$3 near5 ((bias near3 volt\$3) volt\$3))) and power	EPO; JPO; DERWENT; IBM_TDB	2003/06/11 07:40
-	42186	((wafer substrate) near8 (hold\$3 pedestal chuck))	USPAT; US-PGPUB	2003/06/10 18:18
-	18979	((wafer substrate) near8 (hold\$3 pedestal chuck)) and (plasma ion)	USPAT; US-PGPUB	2003/06/10 18:14
-	2322	((wafer substrate) near8 (hold\$3 pedestal chuck)) and (plasma ion) ) and (bias near3 volt\$6)	USPAT; US-PGPUB	2003/06/10 18:14
-	10302	((wafer substrate) near8 (hold\$3 pedestal chuck)) and (plasma ion) ) and (volt\$6)	USPAT; US-PGPUB	2003/06/10 17:23

-	10302	(((((wafer substrate) near8 (hold\$3 pedestal chuck))) and (plasma ion) ) and (bias near3 volt\$6)) (((((wafer substrate) near8 (hold\$3 pedestal chuck))) and (plasma ion) ) and (volt\$6))	USPAT; US-PGPUB	2003/06/10 17:24
-	345	(((((wafer substrate) near8 (hold\$3 pedestal chuck))) and (plasma ion) ) and (bias near3 volt\$6)) (((((wafer substrate) near8 (hold\$3 pedestal chuck))) and (plasma ion) ) and (volt\$6))) and (monitor\$3 near5 ((bias near3 volt\$3) volt\$3))	USPAT; US-PGPUB	2003/06/10 19:40
-	4	(((((wafer substrate) near8 (hold\$3 pedestal chuck))) and (plasma ion) ) and (bias near3 volt\$6)) (((((wafer substrate) near8 (hold\$3 pedestal chuck))) and (plasma ion) ) and (volt\$6))) and (monitor\$3 near5 (ground near3 volt\$3))	USPAT; US-PGPUB	2003/06/10 18:15
-	293	(((((wafer substrate) near8 (hold\$3 pedestal chuck))) and (plasma ion) ) and (bias near3 volt\$6)) (((((wafer substrate) near8 (hold\$3 pedestal chuck))) and (plasma ion) ) and (volt\$6))) and (ground adj3 volt\$3)	USPAT; US-PGPUB	2003/06/10 17:31
-	36	((((((wafer substrate) near8 (hold\$3 pedestal chuck))) and (plasma ion) ) and (bias near3 volt\$6)) (((((wafer substrate) near8 (hold\$3 pedestal chuck))) and (plasma ion) ) and (volt\$6))) and (monitor\$3 near5 ((bias near3 volt\$3) volt\$3))) and ((((((wafer substrate) near8 (hold\$3 pedestal chuck))) and (plasma ion) ) and (bias near3 volt\$6)) (((((wafer substrate) near8 (hold\$3 pedestal chuck))) and (plasma ion) ) and (volt\$6))) and (ground adj3 volt\$3))	USPAT; US-PGPUB	2003/06/10 18:13
-	46843	((wafer substrate) near8 (hold\$3 pedestal chuck))	EPO; JPO; DERWENT; IBM_TDB	2003/06/10 18:13
-	5836	((wafer substrate) near8 (hold\$3 pedestal chuck))) and (plasma ion)	EPO; JPO; DERWENT; IBM_TDB	2003/06/10 18:14
-	1010	((((wafer substrate) near8 (hold\$3 pedestal chuck))) and (plasma ion) ) and ((bias near3 volt\$3) volt\$3)	EPO; JPO; DERWENT; IBM_TDB	2003/06/10 18:14
-	0	(((((wafer substrate) near8 (hold\$3 pedestal chuck))) and (plasma ion) ) and ((bias near3 volt\$3) volt\$3)) and (monitor\$3 near5 (ground near3 volt\$3))	EPO; JPO; DERWENT; IBM_TDB	2003/06/10 18:15
-	4331	((monitor\$3 control\$4 observ\$4) same volt\$3 same(ground near3 current))	USPAT; US-PGPUB	2003/06/10 18:22
-	44	((monitor\$3 control\$4 observ\$4) same volt\$3 same(ground near3 current) same (plasma ion))	USPAT; US-PGPUB	2003/06/10 18:38
-	15	((monitor\$3 control\$4 observ\$4) same volt\$3 same(ground near3 current) same (plasma ion))	EPO; JPO; DERWENT; IBM_TDB	2003/06/10 18:39
-	296	((((((wafer substrate) near8 (hold\$3 pedestal chuck))) and (plasma ion) ) and (bias near3 volt\$6)) (((((wafer substrate) near8 (hold\$3 pedestal chuck))) and (plasma ion) ) and (volt\$6))) and (monitor\$3 near5 ((bias near3 volt\$3) volt\$3))) and power	USPAT; US-PGPUB	2003/06/10 19:41

-	2	(((((((wafer substrate) near8 (hold\$3 pedestal chuck))) and (plasma ion) ) and (bias near3 volt\$6)) (((((wafer substrate) near8 (hold\$3 pedestal chuck))) and (plasma ion) ) and (volt\$6))) and (monitor\$3 near5 ((bias near3 volt\$3) volt\$3))) and power) and (first near5 electromagnetic near5 wave)	USPAT; US-PGPUB	2003/06/10 19:47
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